

## Electronic Supplementary Information

### Creating High Quality Ca:TiO<sub>2</sub>-B (CaTi<sub>5</sub>O<sub>11</sub>) and TiO<sub>2</sub>-B Epitaxial Thin Films by Pulsed Laser Deposition

Kui Zhang, Xianfeng Du, Michael B. Katz, Baihai Li, Sung Joo Kim, Kaixin Song, George W. Graham, and Xiaoqing Pan\*

Department of Materials Science and Engineering  
University of Michigan, Ann Arbor, MI 48109, USA

\* Corresponding author, E-mail: panx@umich.edu

**Table S1.** Lattice structures of the phases and substrates involved in this study.

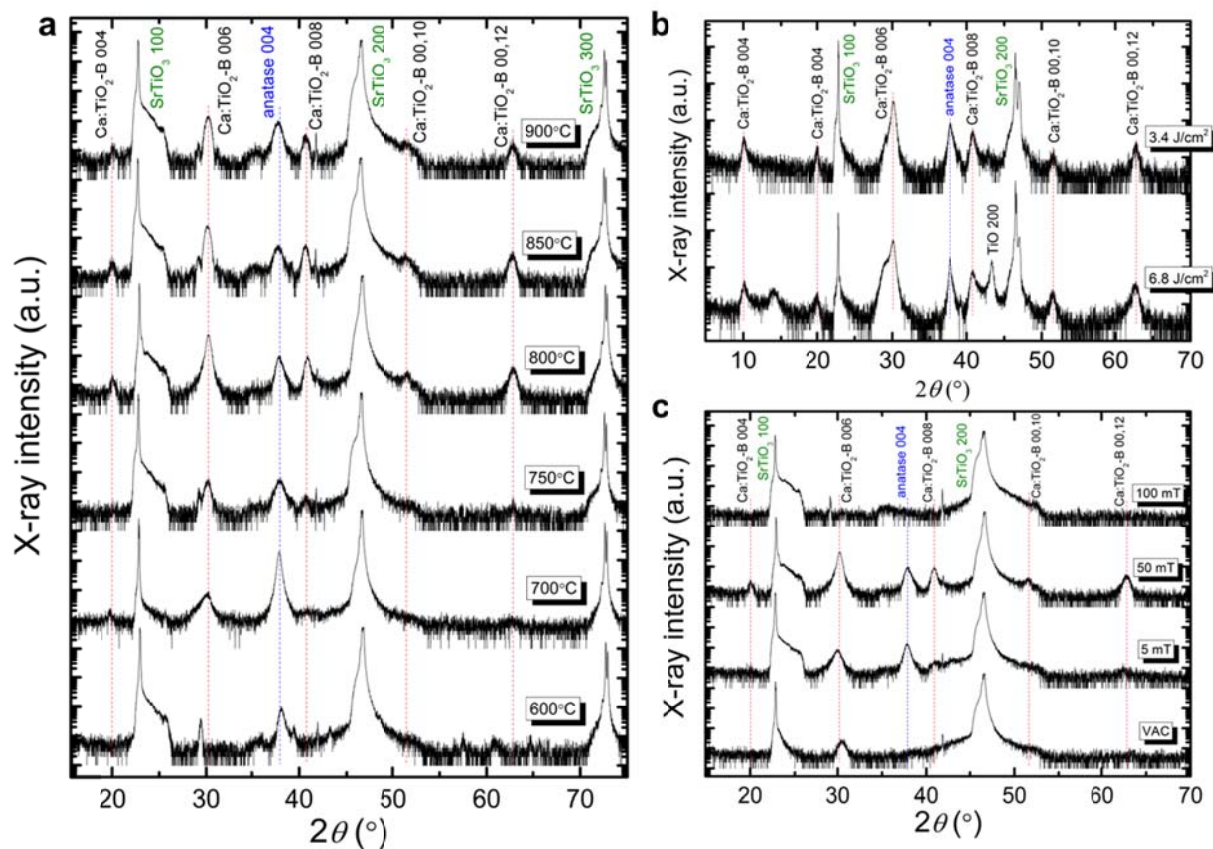
Phase	Crystal system	Lattice parameters
Ca:TiO <sub>2</sub> -B	orthorhombic	$a=12.1702 \text{ \AA}, b=3.8013 \text{ \AA}, c=17.9841 \text{ \AA}$
TiO <sub>2</sub> -B	monoclinic	$a=12.1787 \text{ \AA}, b=3.7412 \text{ \AA}, c=6.5249 \text{ \AA}, \beta=107.054^\circ$
TiO <sub>2</sub> -anatase	tetragonal	$a=b=3.7820 \text{ \AA}, c=9.5150 \text{ \AA}$
TiO <sub>2</sub> -rutile	tetragonal	$a=b=4.5900 \text{ \AA}, c=2.9600 \text{ \AA}$
CaTiO <sub>3</sub>	pseudocubic	$a=3.8917 \text{ \AA}$
SrTiO <sub>3</sub>	cubic	$a=3.9051 \text{ \AA}$
LSAT <sup>a</sup>	cubic	$a=3.8680 \text{ \AA}$
LaAlO <sub>3</sub>	pseudocubic	$a=3.7913 \text{ \AA}$
YSZ <sup>b</sup>	cubic	$a=5.1420 \text{ \AA}$
MgO	cubic	$a=4.2130 \text{ \AA}$
Al <sub>2</sub> O <sub>3</sub>	hexagonal	$a=4.7580 \text{ \AA}, c=12.9910 \text{ \AA}$

<sup>a</sup> (LaAlO<sub>3</sub>)<sub>0.3</sub>(Sr<sub>2</sub>AlTaO<sub>6</sub>)<sub>0.7</sub>; <sup>b</sup> yttria-stabilized zirconia

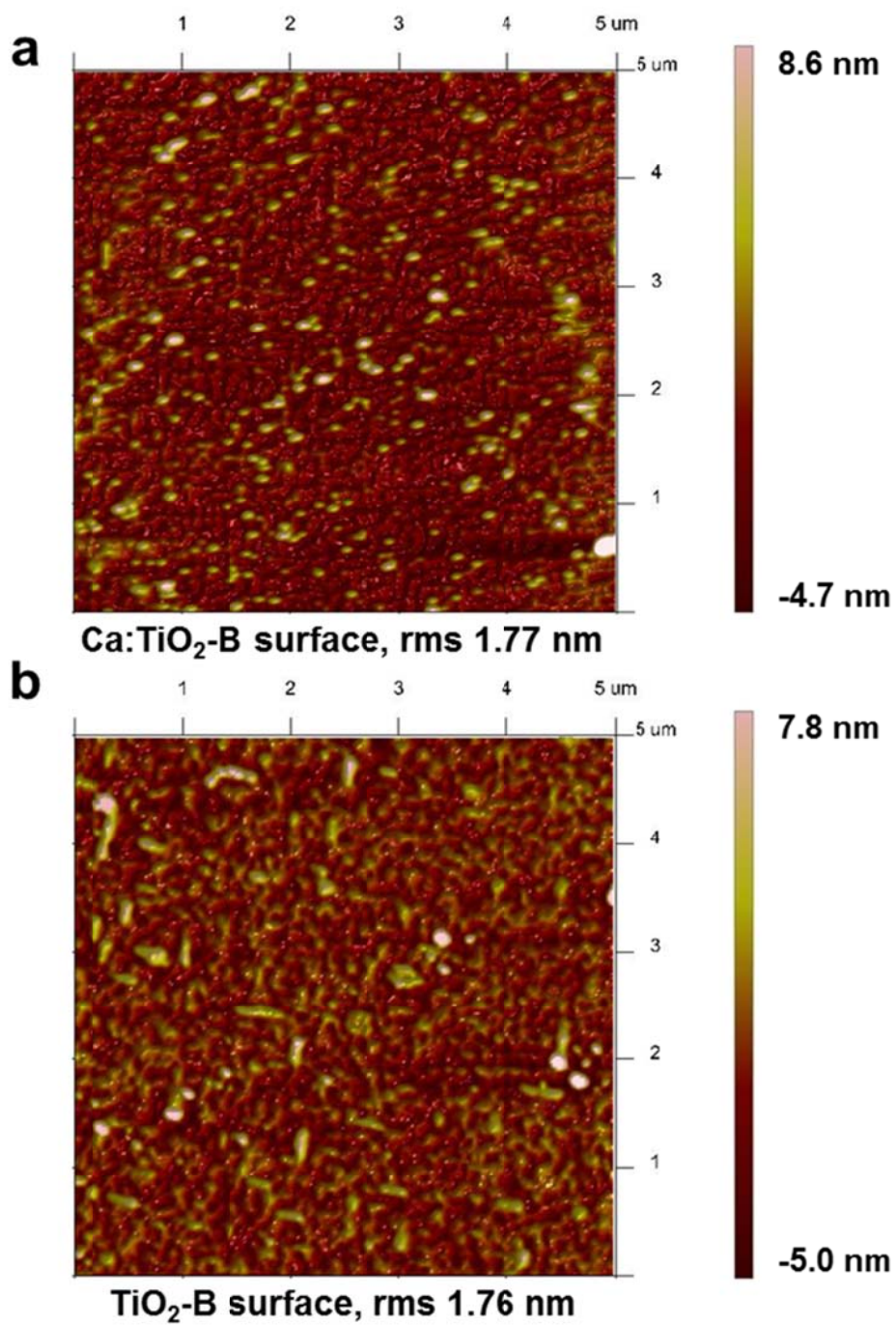
**Table S2.** In-plane mismatch (calculated on a diagonal basis) between difference phases and the substrate surfaces. The preferred phase eventually adopted by the film deposited from a (80% TiO<sub>2</sub> + 20% CaO) target on each specific substrate is set in bold.

Substrate surface	Ca:TiO <sub>2</sub> -B (001)	TiO <sub>2</sub> -anatase (001)	TiO <sub>2</sub> -rutile (001)	CaTiO <sub>3</sub> (001)	TiO <sub>2</sub> -B (001)
SrTiO <sub>3</sub> (001)	<b>3.25%</b>	-3.15%	17.5%	-0.343%	3.17% <sup>a</sup>
LSAT (001)	<b>4.24%</b>	<b>-2.22%</b>	18.7%	0.613%	4.16% <sup>a</sup>
LaAlO <sub>3</sub> (001)	<b>6.35%</b>	<b>-0.245%</b>	21.1%	2.65%	6.27% <sup>a</sup>
YSZ (100)	14.7%	10.3%	<b>-10.7%</b>	13.5%	13.9% <sup>a</sup>
MgO (100)	-4.30%	-10.2%	8.95%	<b>-7.63%</b>	-4.37% <sup>a</sup>
$\alpha$ -Al <sub>2</sub> O <sub>3</sub> (0001)	-22.6%	-11.1%	<b>7.95%</b>	-8.48%	-22.6% <sup>a</sup>
Ca:TiO <sub>2</sub> -B (001)	0	-6.20%	13.8%	-3.48%	<b>-0.075%</b>

<sup>a</sup> For comparison only. TiO<sub>2</sub>-B does not grow directly on these substrates in this study.



**Figure S1.** XRD patterns of the films deposited from a 10% CaO target on (001) SrTiO<sub>3</sub> substrates under different conditions: a) growth temperatures from 600 to 900 °C; b) laser fluence from 3.4 to 6.8 J cm<sup>-2</sup>; c) O<sub>2</sub> partial pressure from vacuum to 100 mTorr. Substrates peaks are labeled in green, anatase peaks in blue. Vertical dashed lines are drawn to mark peak positions for comparison.



**Figure S2.** AFM images (tapping mode) showing the surfaces of a) a (001) Ca:TiO<sub>2</sub>-B film and b) a (001) TiO<sub>2</sub>-B film, respectively. Scan area is 5  $\mu\text{m} \times 5 \mu\text{m}$  for both.